

Erratum: "Epitaxial nucleation of polycrystalline silicon carbide during chemical vapor deposition" [J. Mater. Res. **8**, 1086 (1993)]

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When this article appeared in the May issue of *Journal of Materials Research*, some incorrect fonts were inadvertently used to output the final version of the first two pages (pages 1086 and 1087) of the article.

The following are the corrected pages, output with the appropriate fonts, as they should have appeared in the May issue.